

**INFORMATION DISCLOSURE STATEMENT**

Applicant : Hojo et al.  
App. No : 10/554,380  
Filed : September 29, 2006  
For : POSITIVE PHOTORESIST  
COMPOSITION AND METHOD FOR  
FORMING RESIST PATTERN  
Examiner : Anca Eoff  
Art Unit : 1795

**CERTIFICATE OF EFS WEB  
TRANSMISSION**

I hereby certify that this correspondence, and any other attachment noted on the automated Acknowledgement Receipt, is being transmitted from within the Pacific Time zone to the Commissioner for Patents via the EFS Web server on:

September 5, 2008

(Date)

Neil S. Barfield, Ph.D., Reg. No. 39,901

Mail Stop Amendment  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

Enclosed for filing in the above-identified application is a PTO/SB/08 Equivalent listing 5 (five) references. Please place these documents in the application file.

No fees are believed to be due. However, the Commissioner is hereby authorized to charge any additional fees which may be required to Account No. 11-1410.

Respectfully submitted,

KNOBBE, MARTENS, OLSON & BEAR, LLP

Dated: 9/5/08

By: \_\_\_\_\_

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